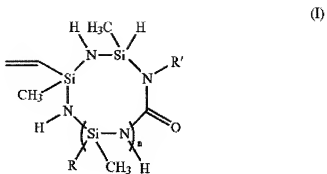


**Amendments to the Claims**

This Listing of Claims will replace all prior versions, and listings, of claims in the application:

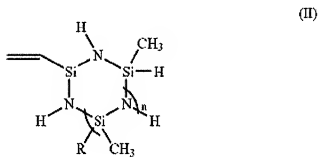
**WHAT IS CLAIMED IS:**

1. (presently amended) A photopolymerizable composition, comprising:
  - (a) at least a first monomer comprising at least one ethylenically unsaturated group, and at least one Si-N linkage, at least one Si-O linkage, and/or at least one Si-C linkage; [[and,]]
  - (b) at least a second monomer comprising at least one thiol functional group;  
and
  - (c) no more than 0.02% by weight of a photoinitiator.
2. (original) The composition according to claim 1, wherein the first monomer comprises at least one vinyl functional group.
3. (original) The composition according to claim 1-or 2, wherein the first monomer comprises at least three Si-N linkages, at least three Si-O linkages, and/or at least one Si-C linkages.
4. (presently amended) The composition according to anyone of claims 1 or 2 ~~claims 1-3~~, wherein the second monomer comprises two or more thiol functional groups.
5. (presently amended) The composition according to anyone of claims 1 or 2 ~~claims 1-4~~, wherein the first monomer is represented by formula (I):



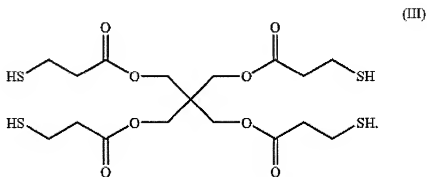
wherein n is an integer from 1-20, R is H or  $\text{CH}=\text{CH}_2$ , and R' is an organic group comprising from 1-20 carbon atoms.

6. (presently amended) The composition according to anyone of claims 1 or 2 ~~claims 1-5~~, wherein the first monomer is optionally represented by formula (II):



where R is H or  $\text{CH}=\text{CH}_2$ , and n is an integer from 1-20.

7. (presently amended) The composition according to anyone of claims 1 or 2 claims 1-6, wherein the second monomer is represented by formula (III):



8. (canceled).

9. (presently amended) A method of forming a ceramic material, the method comprising:

(a) ~~reacting~~ photopolymerizing at least a first monomer comprising at least one ethylenically unsaturated group with at least a second monomer comprising at least one thiol functional group and no more than 0.02 % by weight photoinitiator to form a polymeric material; and,

(b) heating the polymeric material to form the ceramic material.

10. (original) The method according to claim 9, wherein the first monomer comprises at least one vinyl functional group.

11. (original) The method according to claims 9 or 10, wherein the first monomer comprises at least one Si-N linkage, at least one Si-O linkage, and/or at least one Si-C linkage.

12-19. (canceled)

20. (presently amended) A method of forming a three-dimensional ceramic material comprising:

(1) coating a layer of a composition onto a surface, wherein the composition is ~~used as defined in anyone of claims 1-8~~ comprises:

(a) at least a first monomer comprising at least one ethylenically unsaturated group, and at least one of an Si-N linkage, an Si-O linkage and an Si-C linkage;

(b) at least a second monomer comprising at least one thiol functional group; and

(c) no more than 1.0% by weight of a photoinitiator;

(2) exposing the layer imagewise to actinic radiation to form an imaged cross-section, wherein the radiation is of sufficient intensity to cause substantial curing of the layer in the exposed areas;

(3) coating a layer of the composition onto the previously exposed imaged cross-section;

(4) exposing the layer from step (3) imagewise to actinic radiation to form an additional imaged cross-section, wherein the radiation is of sufficient intensity to cause substantial curing of the layer in the exposed areas and to cause adhesion to the previously exposed imaged cross-section;

(5) repeating steps (3) and (4) a sufficient number of times in order to build up a three-dimensional article; and,

(6) pyrolyzing the three dimensional article to form the three dimensional ceramic material.

21. (original) The method according to claim 20, further comprising separating exposed regions of the layer of the composition from unexposed regions of the layer of the composition.

22-24. (canceled)

25. (new) The method according to claim 20, wherein in the composition has no more than 0.02% by weight of a photoinitiator.

26. (new) The method according to claim 20, wherein in the composition has no photoinitiator.

27. (new) The composition according to claim 1 wherein the composition has no photoinitiator.

28. (new) The method according to claim 9 wherein the composition has no photoinitiator.